Product Launch





Nanonex launches new NX 2600-BA tool which combines full wafer nanoimprinter, photolithography aligner, and front side and backside aligner to offer sub-5 nm imprinting resolution and sub-1 micrometer alignment accuracy

Princeton, NJ, Jan. 31. 2010:

Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, is proud to launch its new Nanonex NX-2600 BA tool with full wafer imprint, photolithography alignment, and both front side and backside alignment (BA) capability for supporting the cutting edge micro-/ nano -technologies.

The Nanonex NX-2600 BA is capable of all imprint forms: thermal, photo-curable, embossing and photolithography, with sub-5nm imprinting resolution and sub-1 micrometer alignment accuracy -- a feature currently impossible using other existing lithographic methods. Based on the Nanonex unique patented Air Cushion PressTM technology, the NX-2600 BA provides unsurpassed uniformity regardless of backside topology, wafer or mask flatness, or backside contamination. This ACP technology also eliminates lateral shifting between the mask and substrate, which significantly increases mask lifetime. Moreover, with its unique backside alignment capability, NX 2600 BA offers more opportunities in fabricating and integrating functional micro/nanostructures on both sides of a substrate.

The first NX-2600 BA tool will be installed at the top tier university in U.S within months.

Nanonex Corporation is the inventor of "nanoimprint lithography", the world's first nanoimprint lithography company, and the world's leading provider of nanoimprint solutions that include equipment, masks, resists and consulting services. Nanonex's patented and

proprietary nanoimprint lithography (NIL) solutions and Air-Cushion PressTM can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of industry applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Since 1999, Nanonex has delivered over 60 tools, 300 shipments thermal and UV curable nanoimprint resist and numerous imprint molds. Nanonex also provides first class consulting services to meet customers' application requirements.

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